

FORM PTO-1449 (REV. 7-80)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. 854063.618D1		APPLICATION NO. 101712211	
INFORMATION DISCLOSURE STATEMENT <i>(Use several sheets if necessary)</i>				APPLICANTS Pietro Erratico et al.			
				FILING DATE November 12, 2003		GROUP ART UNIT 0815	
U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL	AA	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
982		3,969,168	07/13/76	Kuhn	156	17	/
982	AB	4,993,143	02/19/91	Sidner	29	621.1	
982	AC	5,773,870	06/30/98	Su et al.	257	531	
982	AD	6,001,666	12/14/99	Diem et al.	438	52	
982	AE	6,015,761	01/18/00	Merry et al.	438	727	
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	<i>class/subclass</i>		TRANSLATION YES NO
982	AF	JP62076783	04/08/87	Japan (Abstract Only)			
982	AG	JP62076784	04/08/87	Japan (Abstract Only)			
982	AH	WO9417558	08/04/94	PCT			
982	AI	0 658 927 A	06/21/95	Europe (+ Abstract)			
982	AJ	960177-7 A	11/10/97	Sweden (+ Abstract)			
982	AK	196 21 349 A	12/04/97	Germany (+ Abstract)			
982	AL	1 043 770 A1	10/11/00	EP			
982	AM	1 130 631 A1	09/05/01	EP			
OTHER PRIOR ART <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>							
982	AN	Schubert, "Method of Making Separate Regions of Various Average Depths with One Anisotropic Etch," Research Disclosure, No. 316, Emsworth, GB, August, 1990, pp. 688-689.					
982	AO	Zou et al., "Single-Chip Fabrication of Integrated Fluid System (IFS), <i>IEEE Workshop on Micro Electro Mechanical Systems</i> , New York, NY: IEEE, 25 January 1998, pp 448-453					
982	AP	"Method of Making Separate Regions of Various Average Depths with one Anisotropic Etch," <i>Research Disclosure, GB, Industrial Opportunities Ltd., Havant, No. 316</i> , August 1990					
982	AQ	Sugiyama et al., "Micro-Diaphragm Pressure Sensor," <i>1986 IEEE</i> , 8.3, 184-IEDM, pp 184-187.					
EXAMINER 982 Ebert				DATE CONSIDERED 10/6/04			
* EXAMINER: Initial if reference considered, whether or not criteria is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant(s).							